

(43) **Pub. Date:** **May 21, 2015**

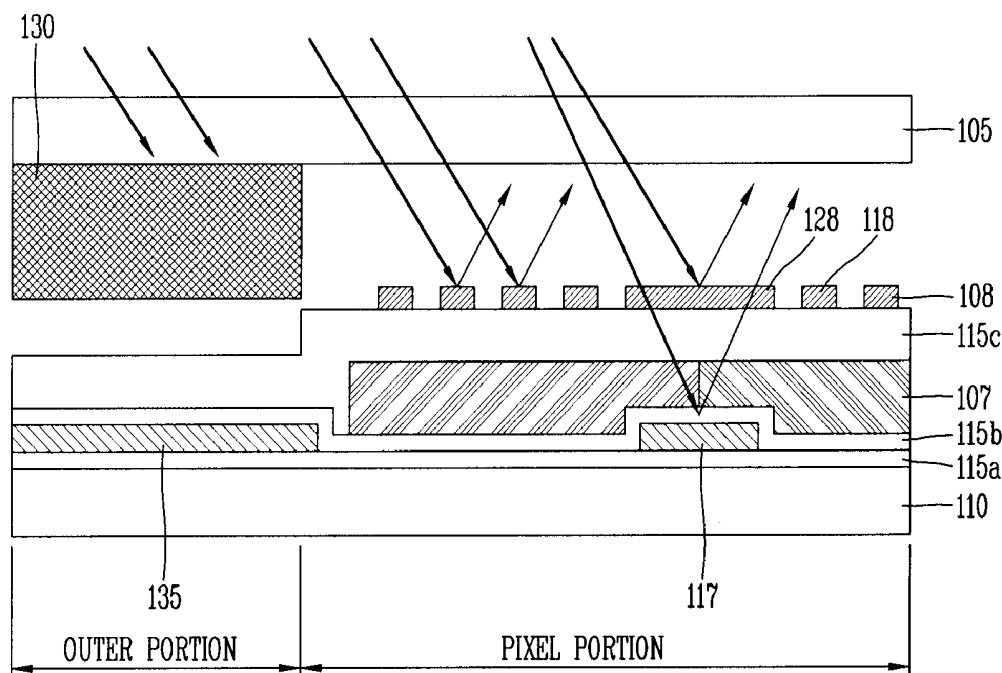


FIG. 1
RELATED ART

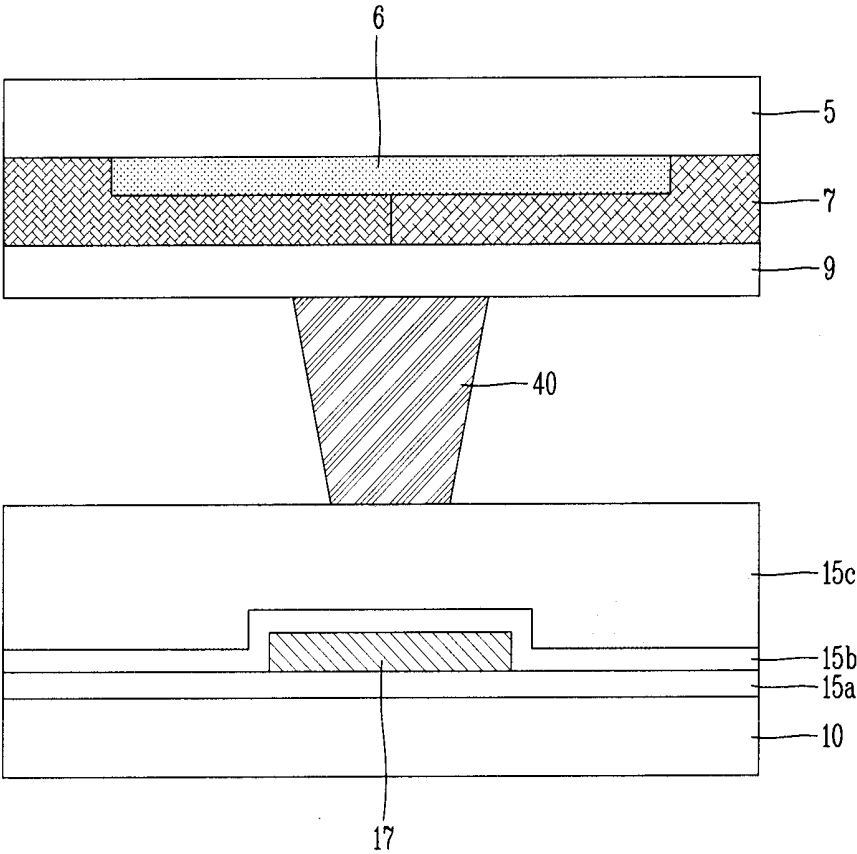


FIG. 2

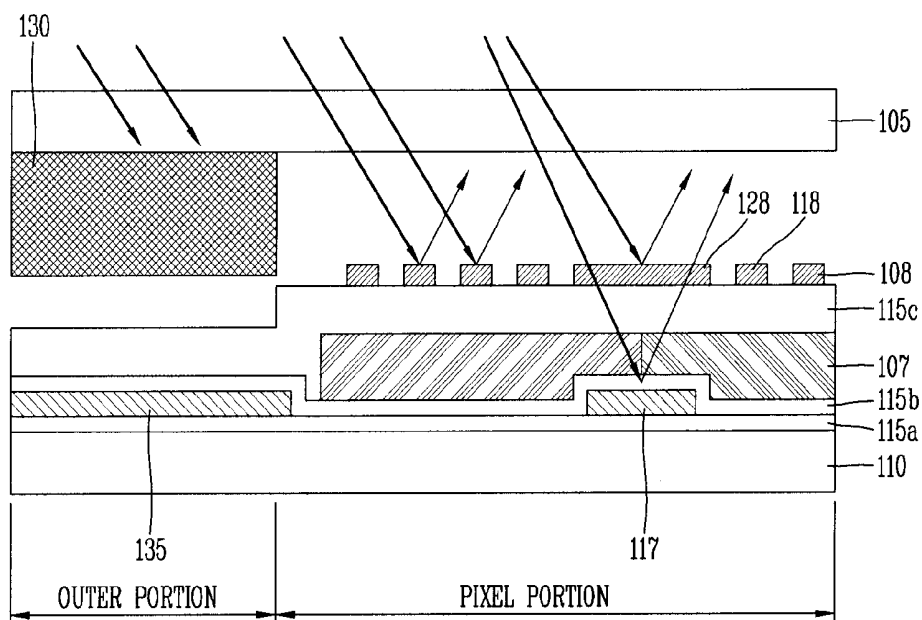


FIG. 3

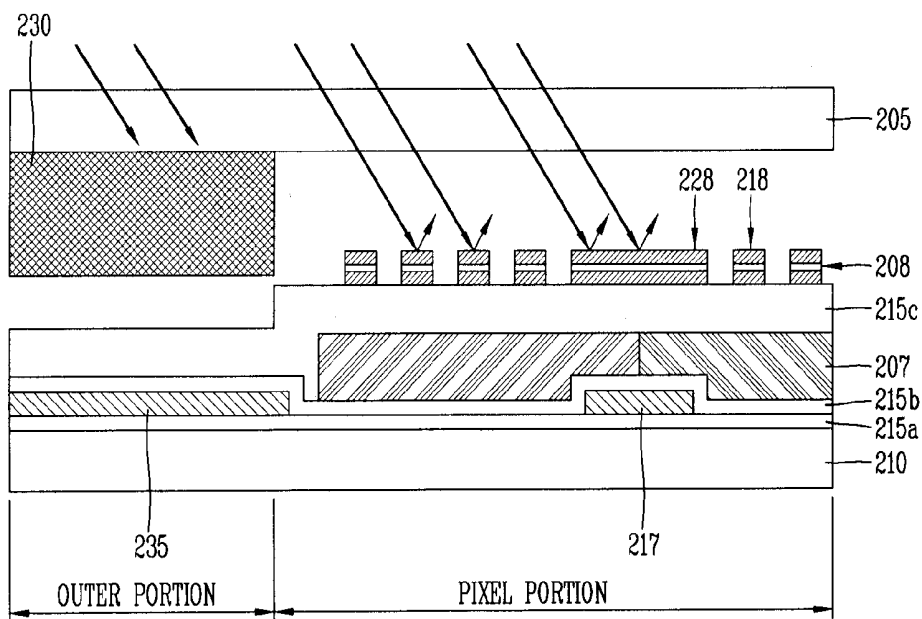


FIG. 5

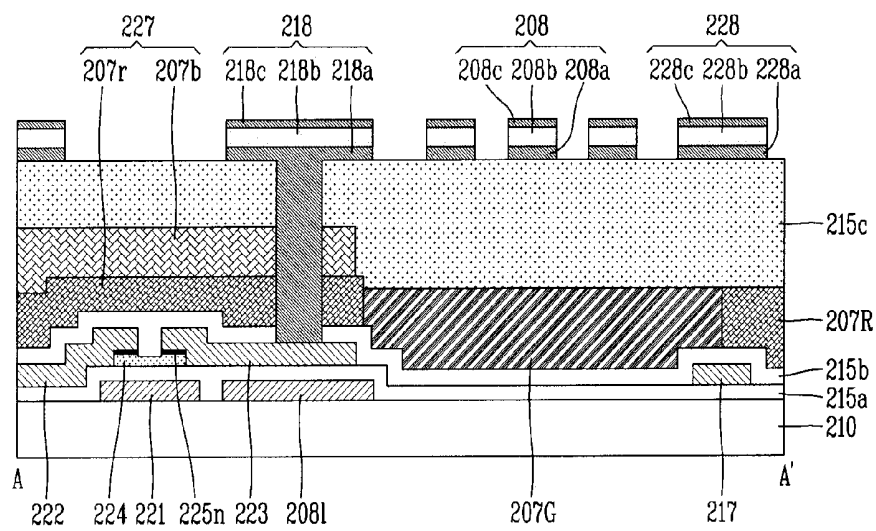


FIG. 6

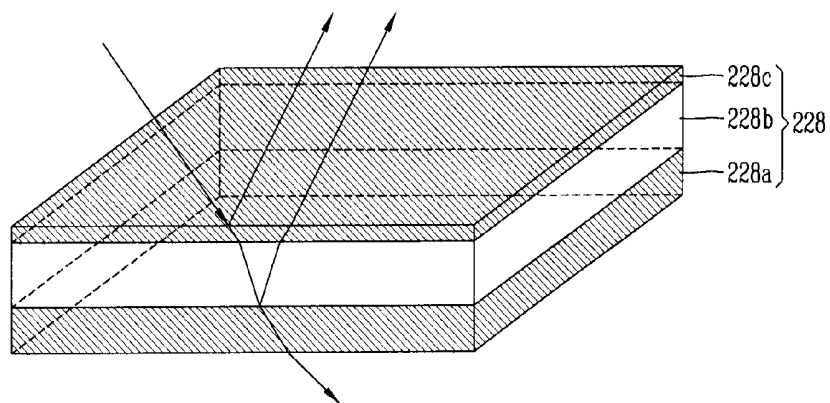


FIG. 7A

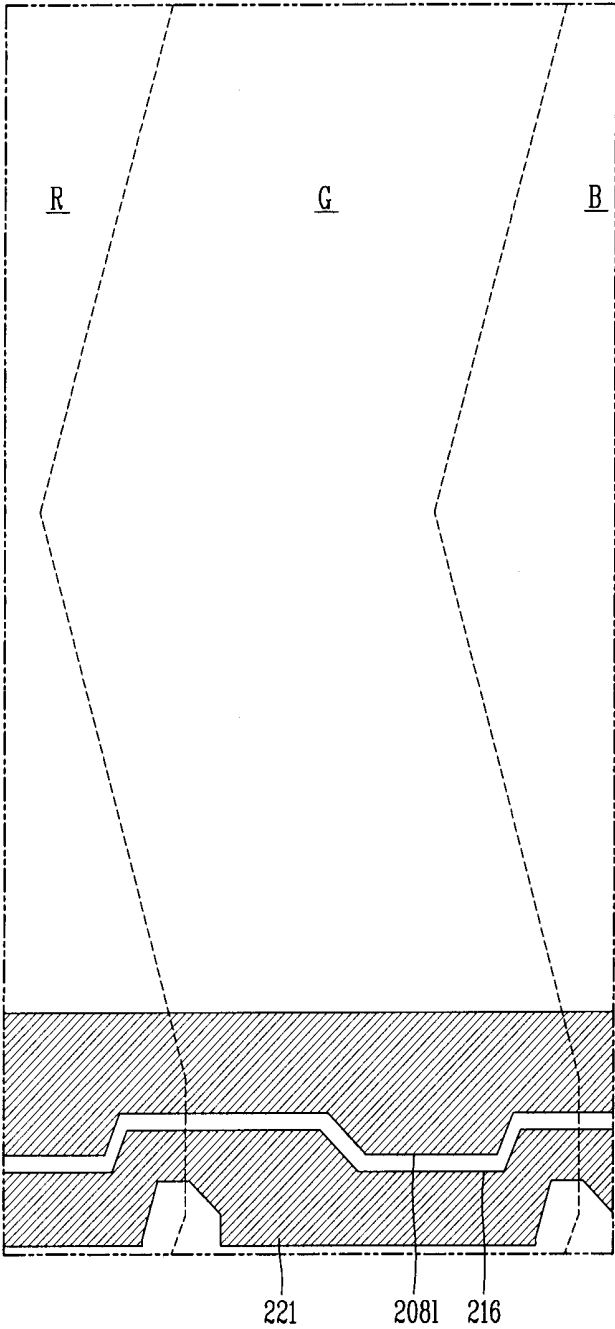


FIG. 7B

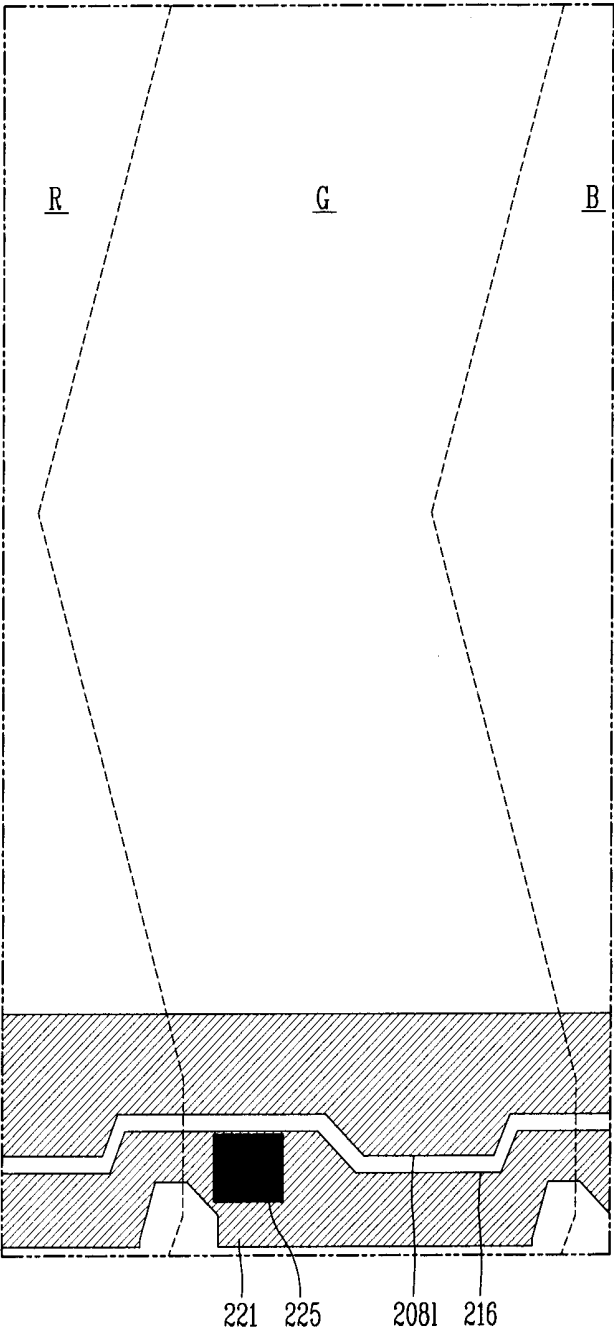


FIG. 7C

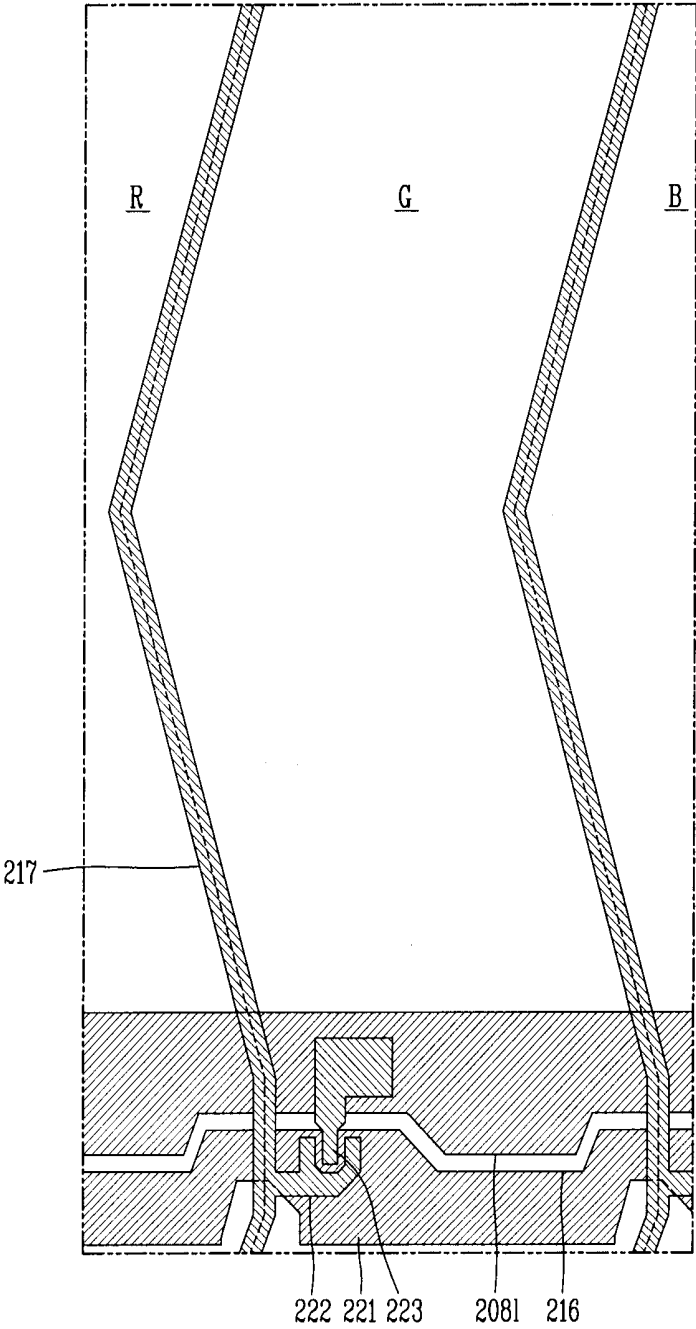


FIG. 7D

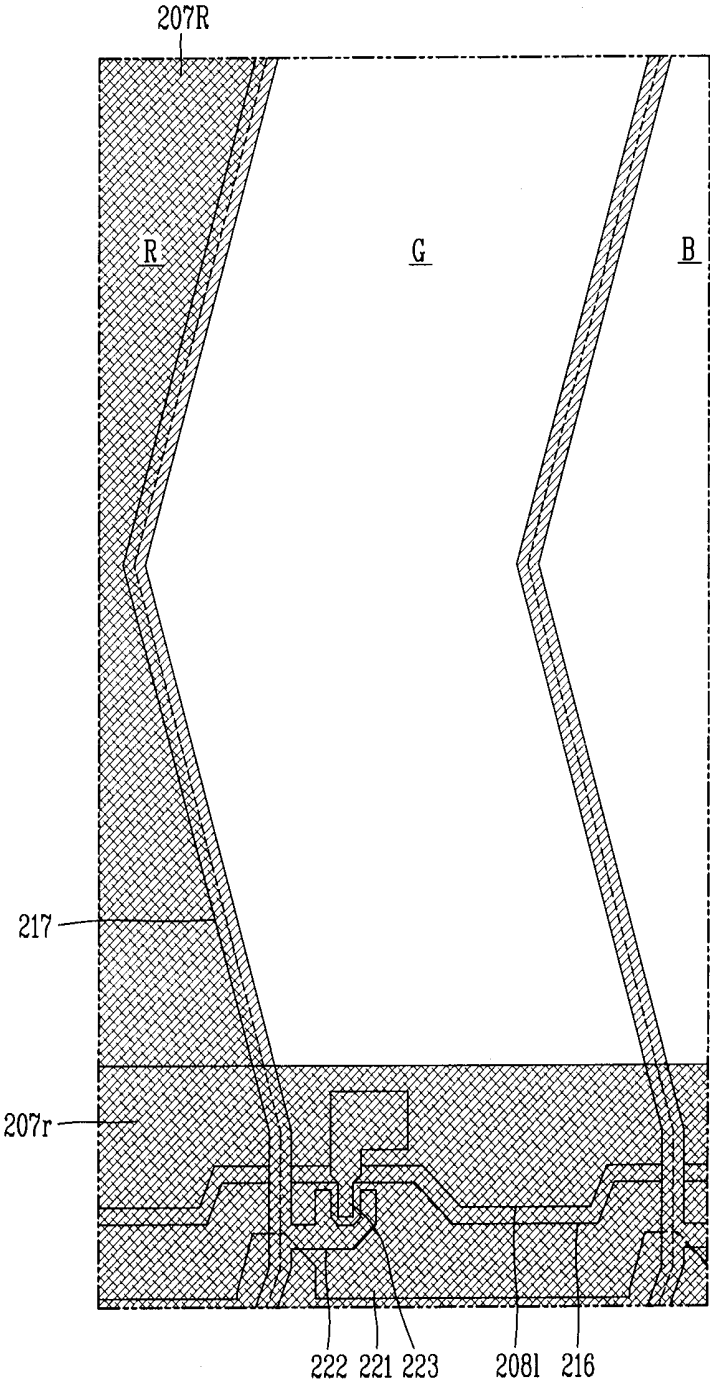


FIG. 7E

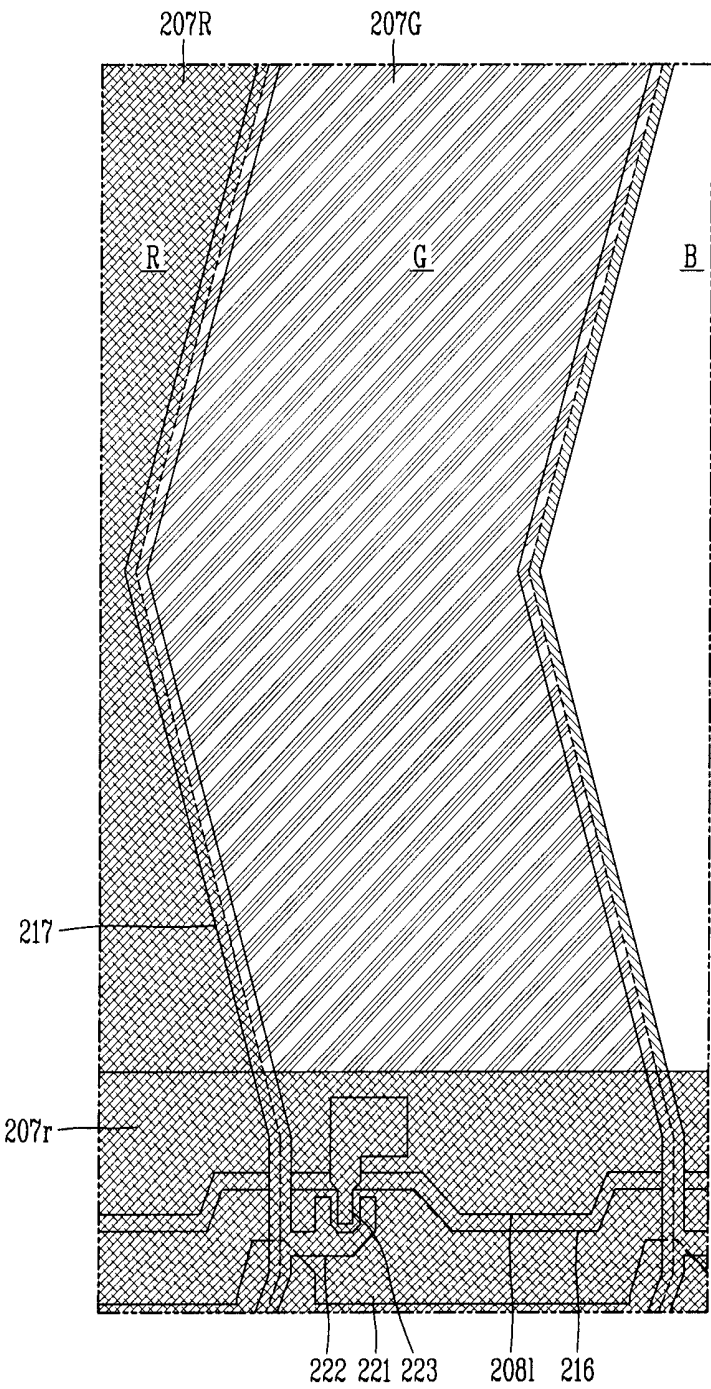


FIG. 7F

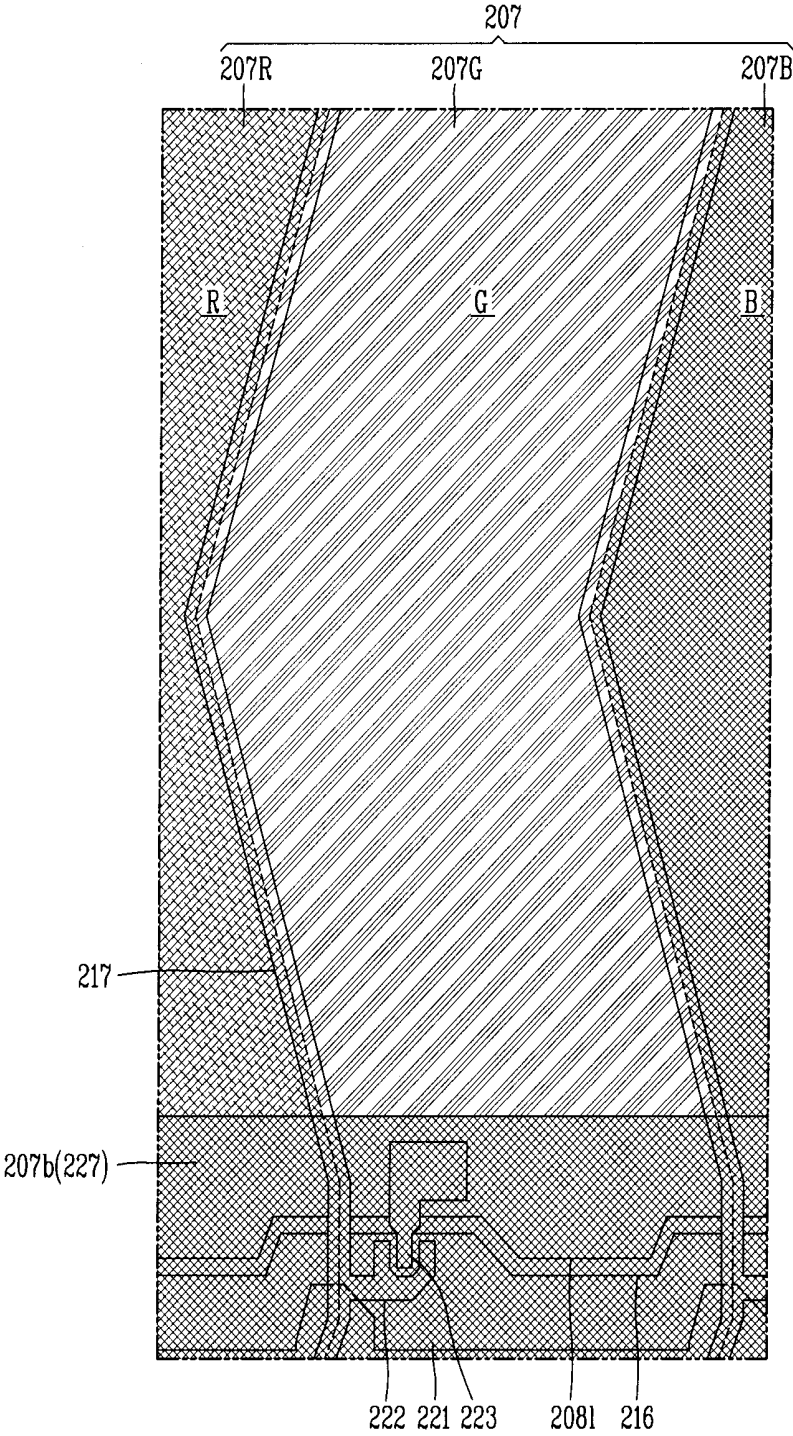


FIG. 7G

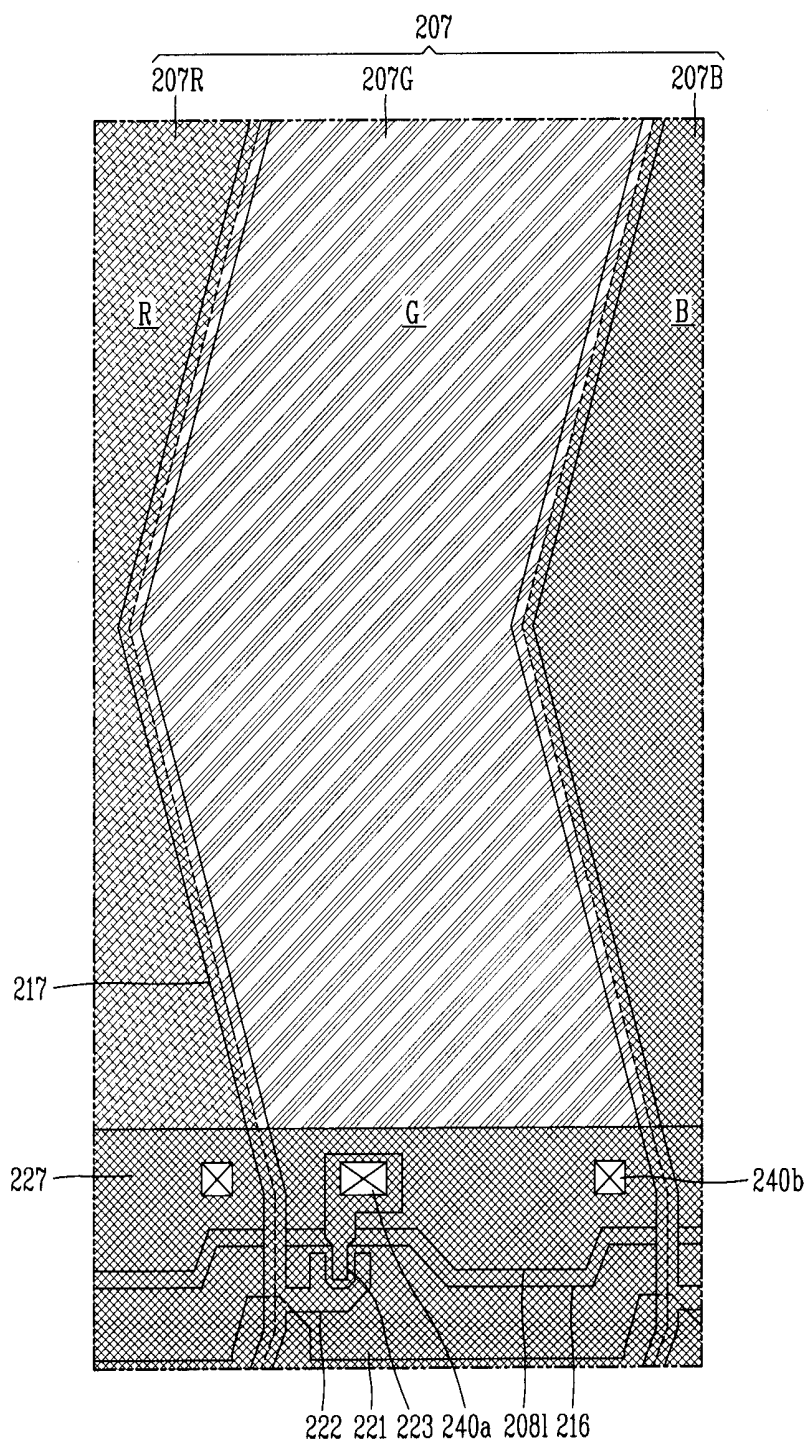


FIG. 7H

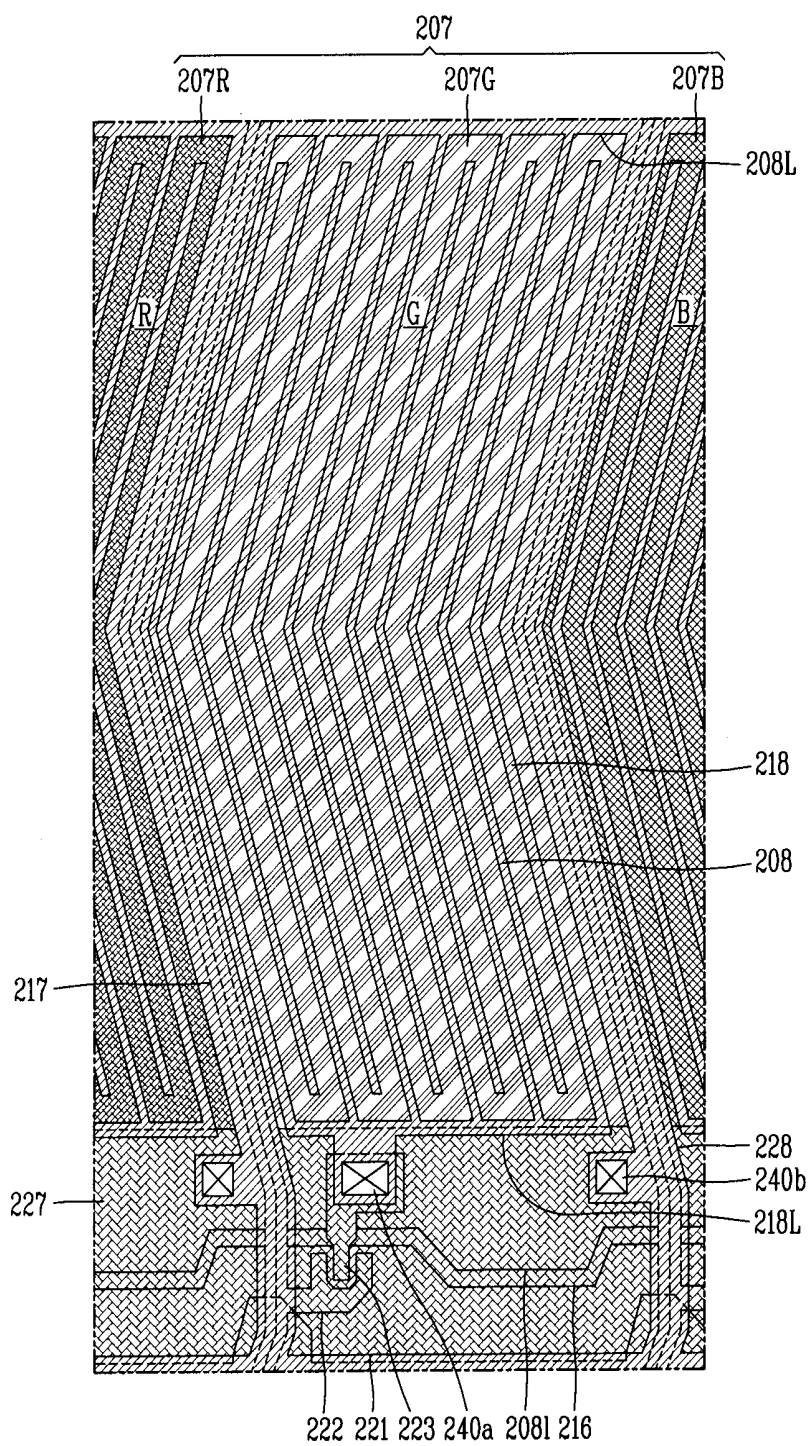


FIG. 8A

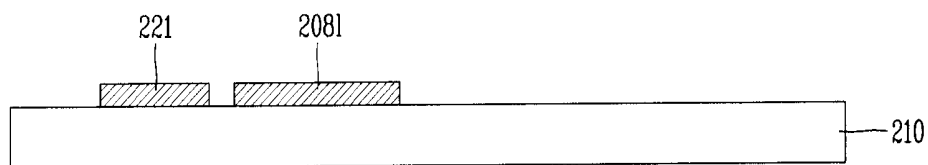


FIG. 8B

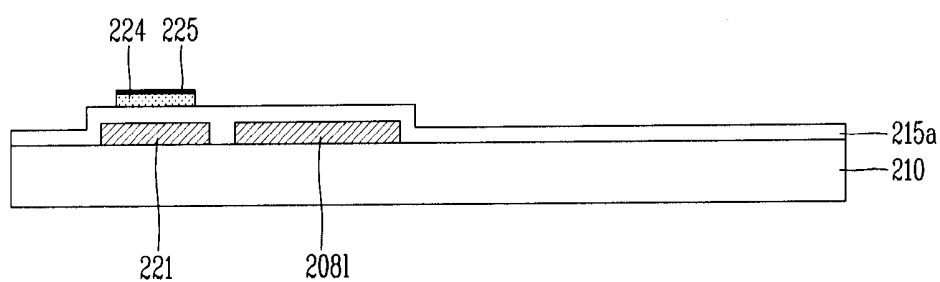


FIG. 8C

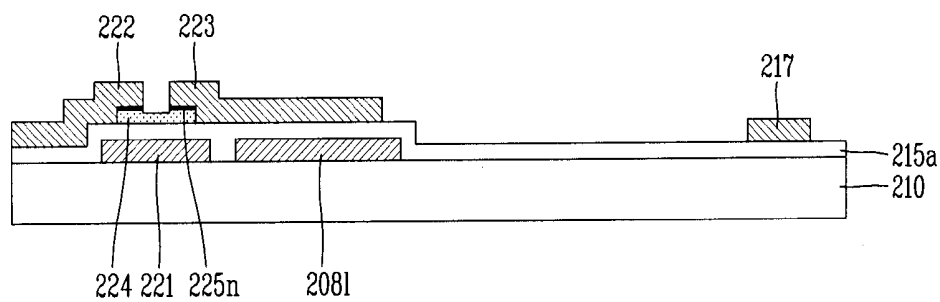


FIG. 8D

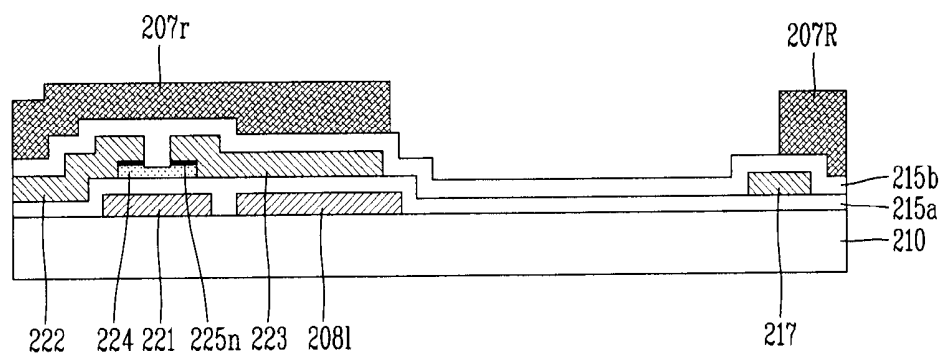


FIG. 8E

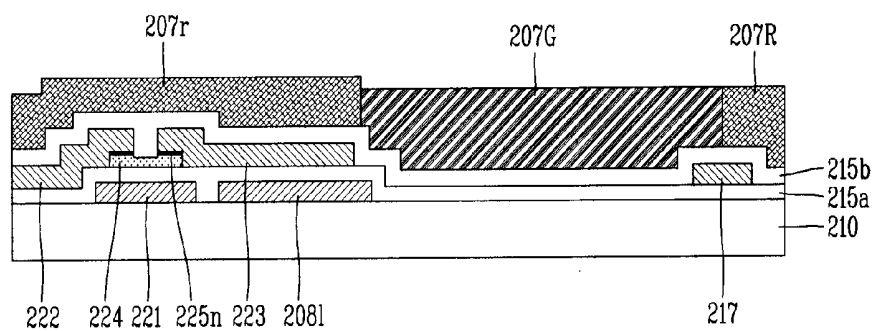


FIG. 8F

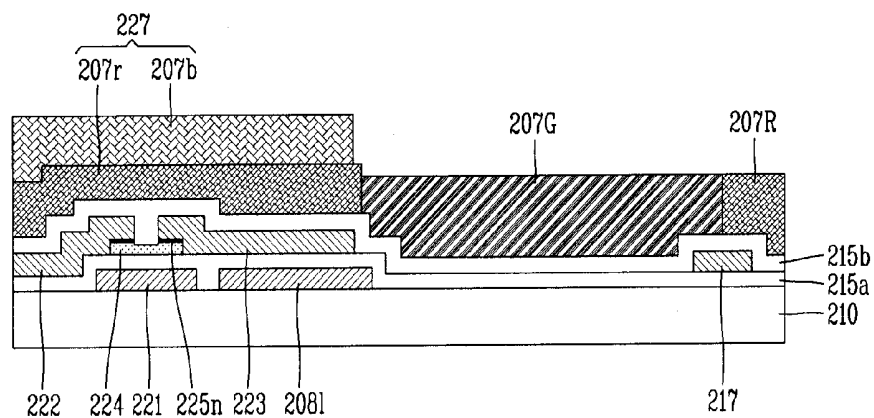


FIG. 8G

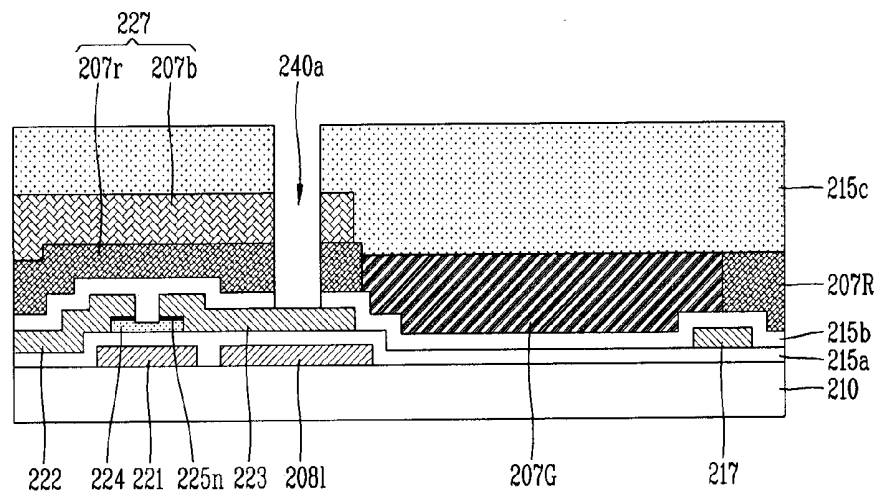


FIG. 8H

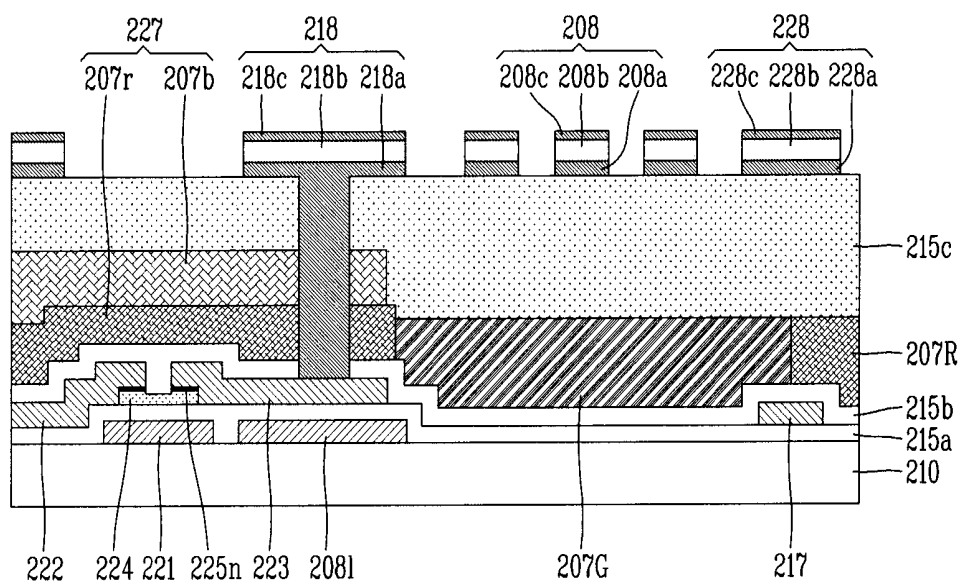
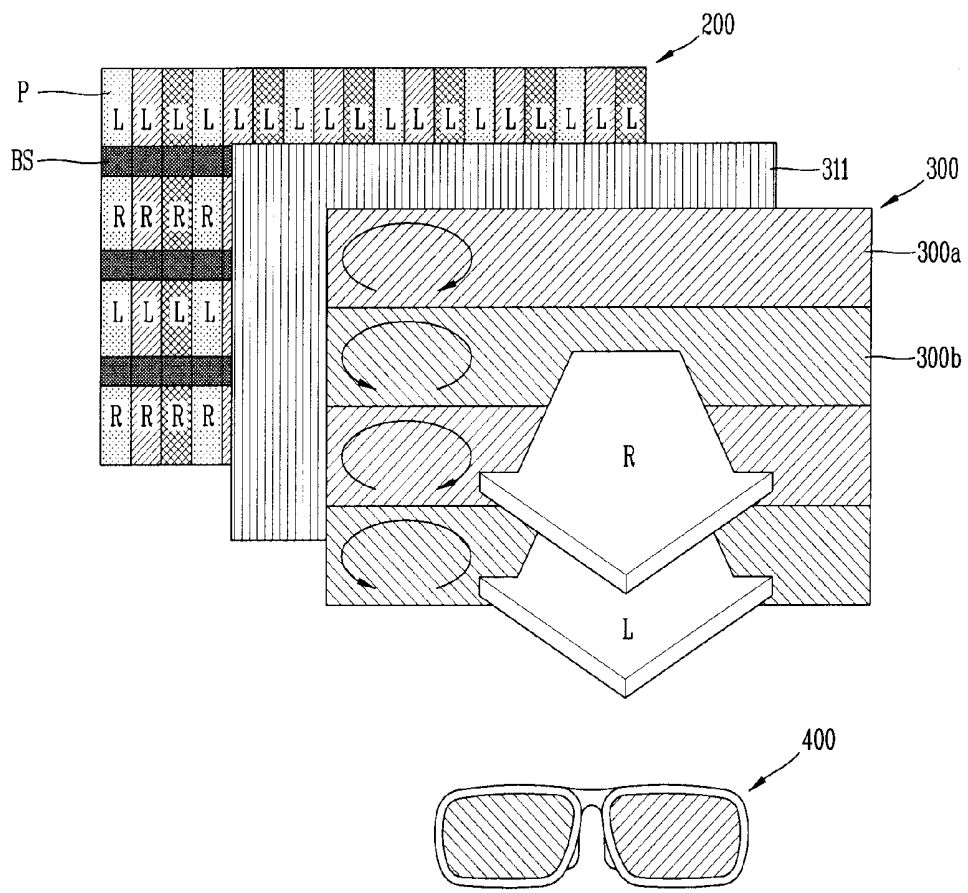


FIG. 9



LIQUID CRYSTAL DISPLAY DEVICE AND METHOD OF FABRICATING THE SAME

CROSS-REFERENCE TO RELATED APPLICATION

[0001] Pursuant to 35 U.S.C. §119(a), this application claims the benefit of earlier filing date and right of priority to Korean Application No. 10-2013-0141701, filed on Nov. 20, 2013, which is incorporated by reference herein in its entirety for all purposes.

BACKGROUND OF THE DISCLOSURE

[0002] 1. Field of the Disclosure

[0003] This specification relates to a liquid crystal display device and a method of fabricating the same. More particularly, the specification relates to a liquid crystal display device having a color filter on TFT (COT) structure in which color filters, along with a thin film transistor, are formed on an array substrate, and a method of fabricating the same.

[0004] 2. Background of the Disclosure

[0005] In general, a liquid crystal display device displays a desired image by individually providing data signals corresponding to image information to pixels arranged in a matrix form and controlling the light transmittance of the pixels.

[0006] Accordingly, the liquid crystal display device includes both a liquid crystal display panel where pixels are arranged in a matrix form and a driving unit for driving the pixels.

[0007] The liquid crystal display panel includes a thin film transistor array substrate and a color filter substrate which face each other and are attached such that they have a uniform cell gap therebetween and a liquid crystal layer in the cell gap.

[0008] A common electrode and a pixel electrode are formed on the liquid crystal display panel in which the array substrate and the color filter substrate are attached to each other in order to apply an electric field to the liquid crystal layer.

[0009] When a voltage of a data signal supplied to the pixel electrode is controlled such that a voltage is supplied to the common electrode, liquid crystal in the liquid crystal layer rotates due to a dielectric anisotropy according to the electric field formed between the common electrode and the pixel electrode. As a result, light is transmitted or blocked in each pixel thereby displaying a character or an image.

[0010] FIG. 1 is a view schematically showing a cross-section structure of a general liquid crystal device, which takes part of the cross-section structure of a data line area as an example.

[0011] Referring to FIG. 1, the general liquid crystal display device includes two glass substrates 5 and 10 and a liquid crystal layer (not shown) formed between the two glass substrates 5 and 10, with a cell gap maintained between them by a column spacer 40.

[0012] A gate line (not shown) and a data line 17 arranged in a matrix and defining pixel regions are formed on the lower glass substrate 10, and a thin film transistor, which is a switching element, is formed at the crossing of the gate line and the data line 17.

[0013] For an in-plane switching (IPS) mode, although not shown, a plurality of pixel electrodes and common electrodes for forming an electric field are alternately arranged within the pixel regions.

[0014] The thin film transistor includes a gate electrode connected to the gate line, a source electrode connected to the data line 17, and a drain electrode connected to a pixel electrode. Further, the thin film transistor includes a plurality of insulation films 15a, 15b, and 15c for insulation between these components and an active pattern that forms a conductive channel between the source electrode and the drain electrode by a gate voltage supplied to the gate electrode.

[0015] A color filter array is formed on the upper glass substrate 5, and the color filter array includes a black matrix 6, color filters 7, and an overcoat layer 9.

[0016] The general LCD device thus configured can bring about improvements in productivity and profitability as the size of a mother substrate for manufacturing a liquid crystal panel becomes larger, but has reduced the aperture ratio due to the increase in an attachment margin, that is, the width of the black matrix 6, in the manufacture of a liquid crystal panel. This lowers luminance and limits resolution, thus causing a decline in competitiveness.

SUMMARY OF THE DISCLOSURE

[0017] An aspect of the detailed description is to provide a liquid crystal display device having a color filter on TFT (COT) structure in which color filters, along with a thin film transistor, are formed on an array substrate, and a method of fabricating the same.

[0018] Another aspect of the detailed description is to provide a liquid crystal display device having a COT structure, which can improve the picture quality and luminance of a display as well as its performance by eliminating a black matrix, and a method of fabricating the same.

[0019] Additional features of the present invention will be described in configurations of the present invention and the appended claims that will be described below.

[0020] To achieve these and other advantages and in accordance with the purpose of this specification, as embodied and broadly described herein, there is provided a method of fabricating a liquid crystal display device, the method including the steps of: forming a gate line and a data line that cross each other on a first substrate to define red, green, and blue pixel regions; forming a thin film transistor at the crossing of the gate line and the data line; forming red, green, and blue color filters within the red, green, and blue pixel regions of the first substrate where the thin film transistor is formed; forming a light blocking layer at the upper and lower boundaries of the pixel regions by laminating color pigments for the red, green, and blue color filters; forming a plurality of common electrodes and pixel electrodes within the pixel regions of the first substrate where the red, green, and blue color filters and the light blocking layer are formed; forming a light blocking pattern at left and right boundaries of the pixel regions over the data line; and attaching the first substrate and a second substrate together, wherein the common electrodes, the pixel electrodes, and the light blocking pattern have a triple-layer structure consisting of lower and upper layers with low reflection and transmission characteristics and an intermediate layer which is light-transmissive.

[0021] The method may further include the step of forming a common line in parallel with the gate line so as to be adjacent to the upper or lower side of the gate line.

[0022] In another aspect of the present invention, there is provided a liquid crystal display device including: a gate line and a data line formed on a first substrate and crossing each other to define red, green, and blue pixel regions; a thin film

transistor formed at the crossing of the gate line and the data line; red, green, and blue color filters formed within the red, green, and blue pixel regions of the first substrate where the thin film transistor is formed; a light blocking layer formed at and lower boundaries of the pixel regions by laminating color pigments for the red, green, and blue color filters; a plurality of common electrodes and pixel electrodes formed within the pixel regions of the first substrate where the red, green, and blue color filters and the light blocking layer are formed; a light blocking pattern formed at left and right boundaries of the pixel regions over the data line; and a second substrate attached to the first substrate and facing each other, wherein the common electrodes, the pixel electrodes, and the light blocking pattern have a triple-layer structure consisting of lower and upper layers with low reflection and transmission characteristics, and an intermediate layer which is light-transmissive.

[0023] The liquid crystal display device may further include a common line that is formed in parallel with the gate line so as to be adjacent to the upper or lower side of the gate line.

[0024] One end of the common electrodes and one end of the light blocking pattern may be connected to a common electrode line, which is in parallel with the gate line, and the common electrode line may be electrically connected to the underlying common line.

[0025] One end of the pixel electrodes may be connected to a pixel electrode line, which is in parallel with the gate line, and the pixel electrode line may be electrically connected to the drain electrode of the thin film transistor.

[0026] The upper and lower layers of the common electrodes, pixel electrodes, and light blocking pattern may be made of an opaque conductive material such as ceramic, metal oxide, MoTi, or copper.

[0027] The intermediate layers of the common electrodes, pixel electrodes, and light blocking pattern may be made of a transparent conductive material such as indium tin oxide (ITO) or indium zinc oxide (IZO).

[0028] The light blocking layer may have a lamination structure of red and blue color layers made of color pigments for the red and blue color filters.

[0029] It is to be understood that both the foregoing general description and the following detailed description are exemplary and explanatory and are intended to provide further explanation of the invention as claimed.

BRIEF DESCRIPTION OF THE DRAWINGS

[0030] The accompanying drawings, which are included to provide a further understanding of the disclosure and are incorporated in and constitute a part of this specification, illustrate exemplary embodiments and together with the description serve to explain the principles of the disclosure.

[0031] In the drawings:

[0032] FIG. 1 is a view schematically showing a cross-section structure of a general liquid crystal display device;

[0033] FIG. 2 is a view schematically showing an example of a cross-section structure of a liquid crystal display device according to an embodiment of the present invention;

[0034] FIG. 3 is a view schematically showing another example of the cross-section structure of the liquid crystal display device according to the present invention;

[0035] FIG. 4 is a top plan view schematically showing part of the array substrate of the liquid crystal display device according to the embodiment of the present invention;

[0036] FIG. 5 is a view schematically showing a cross-section taken along the line A-A' on the array substrate of FIG. 4 according to the embodiment of the present invention;

[0037] FIG. 6 is a view illustrating a triple-layer structure of the light blocking pattern in the liquid crystal display device according to the embodiment of the present invention;

[0038] FIGS. 7A to 7H are top plan views sequentially showing a fabrication process of the array substrate of FIG. 5 according to an embodiment of the present invention;

[0039] FIGS. 8A to 8H are cross-sectional views sequentially showing a fabrication process of the array substrate of FIG. 5 according to an embodiment of the present invention; and

[0040] FIG. 9 is a view illustrating the structure of a stereoscopic image display device using the liquid crystal display device of the present invention as an image panel.

DETAILED DESCRIPTION OF THE DISCLOSURE

[0041] Hereinafter, a liquid crystal display device and a method of fabricating the same according to a preferred embodiment of the present invention will be described with reference to the accompanying drawings so that those skilled in the art can easily practice the invention.

[0042] Advantages and features of the present invention and methods of accomplishing the same may be understood more readily by reference to the following detailed description of preferred embodiments and the accompanying drawings. The present invention may, however, be embodied in many different forms and should not be construed as being limited to the embodiments set forth herein. Rather, these embodiments are provided so that this disclosure will be thorough and complete and will fully convey the concept of the invention to those skilled in the art, and the present invention will only be defined by the appended claims. In the drawings, the size and relative sizes of layers and regions may be exaggerated for clarity.

[0043] It will be understood that when an element or a layer is referred to as being "on" or "over" another element or layer, it can be directly on or directly over the other element, or intervening elements may also be present. In contrast, when an element is referred to as being "directly on" or "directly over" another element, there are no intervening elements present.

[0044] Spatially relative terms, such as "below", "beneath", "lower", "above", "upper", and the like, may be used herein for ease of description to describe one element or feature's relationship to another element(s) or feature(s) as illustrated in the figures. It will be understood that the spatially relative terms are intended to encompass different orientations of the device in use or operation, in addition to the orientation depicted in the figures. For example, if an element illustrated in the drawings is turned over, the element described to be "below" or "beneath" another element may be put "above" the other element. Accordingly, the exemplary wording "below" may include both directions corresponding to "below" and "above".

[0045] The terms used in the present specification are used to describe example embodiments of inventive concepts, and not to limit the inventive concepts. A singular form may include a plural form, unless otherwise defined. The term "comprise" and/or "comprising" specify the existence of mentioned components, steps, operations and/or elements

thereof, and do not exclude existence or addition of one or more components, steps, operations and/or elements thereof.

[0046] FIG. 2 is a view schematically showing an example of a cross-section structure of a liquid crystal display device according to an embodiment of the present invention, which takes part of the cross-section structure of an edge region of a pixel portion as an example.

[0047] Referring to FIG. 2, the liquid crystal display device according to the embodiment of the present invention includes two substrates **105** and **110** divided into a pixel portion and an outer portion and a liquid crystal layer (not shown) formed between them.

[0048] A gate line (not shown) and a data line **117** arranged in a matrix and defining pixel regions are formed in the pixel portion of the lower array substrate **110**, and a thin film transistor, which is a switching element, is formed at the crossing of the gate line and the data line **117**.

[0049] For an in-plane switching (IPS) mode, for example, although not shown, a plurality of pixel electrodes **108** and common electrodes **118** for forming an electric field are alternately arranged within the pixel regions.

[0050] Although not shown, the thin film transistor includes a gate electrode connected to the gate line, a source electrode connected to the data line **117**, and a drain electrode electrically connected to a pixel electrode **118**. Further, the thin film transistor includes a plurality of insulation films **115a**, **115b**, and **115c** for insulation between these components and an active pattern that forms a conductive channel between the source electrode and the drain electrode by a gate voltage supplied to the gate electrode.

[0051] The array substrate **110** thus configured has a color filter on TFT (COT) structure in which color filters **107** are formed on the thin film transistor.

[0052] A predetermined circuit line **135** may be formed in the outer portion of the array substrate **110**. A black column spacer (BCS) **130** is formed in the outer portion of the upper substrate **105**, thereby preventing light from the backlight from leaking out to the bezel portion of the liquid crystal panel.

[0053] The liquid crystal display device according to the embodiment of the present invention thus configured is characterized in that, instead of eliminating the existing black matrix, a light blocking pattern **128** made of an opaque conductive material is formed at the left and right boundaries of the pixel regions, i.e., in horizontal black matrix regions and color pigments are laminated at the upper and lower boundaries of the pixel regions, i.e., in vertical black matrix regions.

[0054] The light blocking pattern **128** is formed over the data line **117** to cover the data line **117**, thereby preventing color interference between neighboring sub-pixels.

[0055] The light blocking pattern **128** may be made of a conductive material having low reflection characteristics, similar to a material for the common electrodes **108** and the pixel electrodes **118**, when internal electrodes, i.e., the common electrodes **108** and the pixel electrodes **118**, are formed on the array substrate **110**.

[0056] For example, an opaque conductive material such as copper Cu, aluminum Al, molybdenum Mo, or molybdenum alloy and a transparent conductive material such as indium tin oxide (ITO) are commonly used as the existing wiring electrode. Regarding a general model using a black matrix, there has been no issue with the optical characteristics of electrodes since the black matrix acts as a blocking film.

[0057] For the development of display products, however, it is necessary to meet the demand for high performance and high quality and strengthen price competitiveness by lowering costs.

[0058] To this end, various efforts are being made in many areas including materials, process development, and design improvement. Consequently, a black-matrix-less model has been developed in order to improve the luminance of display products and the efficiency of backlights by improvement in transmittance in the development of high-performance, high-quality display products.

[0059] However, the black-matrix-less model has more electrode-exposing regions, so the high reflectance of highly-conductive electrodes may affect picture quality and luminance. That is, the aforementioned opaque conductive material is glossy and highly reflective by nature, whereas transparent conductive material has low reflectance but is not applicable in terms of contrast ratio due to its high transmittance.

[0060] Moreover, the difference between the reflectance of the electrodes (i.e., the internal electrodes **108** and **118** and light blocking pattern **128**) in the pixel portion and the reflectance of the outer portion necessarily leads to a luminance difference. That is, in a black-matrix-less COT model, the internal electrodes **108** and **118** and the light blocking pattern **128** also serve as a black matrix, and a luminance difference (~level 4.0) occurs due to the difference between the reflectance (~61%) of the internal electrodes **108** and **118** and light blocking pattern **128** in the black matrix regions of the pixel portion and the reflectance (~0%) of the black column spacer **130** in the outer portion.

[0061] In view of this, it is necessary to develop electrode materials having excellent optical characteristics, such as low reflectance and low transmittance, and high reflection characteristics, in order to improve picture quality and increase the luminance of products

[0062] Hereupon, the internal electrodes and light blocking pattern, which substitute for the black matrix, are formed in, for example, a triple-layer structure according to the present invention. This will be described below in detail by taking another example.

[0063] FIG. 3 is a view schematically showing another example of the cross-section structure of the liquid crystal display device according to the present invention, which takes part of the cross-section structure of an edge region of the pixel portion as an example.

[0064] FIG. 4 is a top plan view schematically showing part of the array substrate of the liquid crystal display device according to the embodiment of the present invention, which takes part of the components on the array substrate of an in-plane switching mode liquid crystal display device as an example. However, the present invention is not limited to this in-plane switching mode liquid crystal display device.

[0065] While, in the actual liquid crystal display device, (M×N) sub-pixels are present at the crossings of N gate lines and M data lines, this figure illustrates only one pixel consisting of red, green, and blue sub-pixels R, G, and B.

[0066] FIG. 5 is a view schematically showing a cross-section taken along the line A-A' on the array substrate of FIG. 4 according to the embodiment of the present invention.

[0067] As shown in FIGS. 4 and 5, if the common electrodes and the pixel electrodes have a bent structure, the liquid crystal molecules are arranged in two directions and form two domains, which gives a wider viewing angle compared to a

mono-domain structure. However, the present invention is not limited to the in-plane switching mode liquid crystal display device having a two-domain structure, but is applicable to any in-plane switching mode liquid crystal display device having a multi-domain structure with two or more domains. Also, the common electrodes and pixel electrodes of the present invention may have a structure other than the bent structure.

[0068] Referring to FIGS. 3 to 5, the liquid crystal display device according to an embodiment of the present invention may include two substrates **205** and **210** divided into a pixel portion and an outer portion and a liquid crystal layer (not shown) formed between the two substrates.

[0069] A gate line **216** and a data line **217** arranged in a matrix and defining pixel regions are formed in the pixel portion of the lower array substrate **210**. That is, the gate line **216** supplies a scan signal from a gate driver (not shown), and the data line **217** supplies a video signal from a data driver (not shown). The gate line **216** and the data line **217** cross each other with a gate insulation film **215a** interposed between them, thereby defining pixel regions.

[0070] A thin film transistor, which is a switching element, is formed at the crossing of the gate line **216** and the data line **217**. A plurality of pixel electrodes **218** and common electrodes **208** for forming an electric field and driving the liquid crystal molecules are alternately arranged within the pixel regions.

[0071] A predetermined circuit line **235** may be formed in the outer portion of the array substrate **210**. A black column spacer (BCS) **230** is formed in the outer portion of the upper substrate **205**, thereby preventing light from the backlight from leaking out to the bezel portion of the liquid crystal panel.

[0072] The thin film transistor responds to a scan signal of the gate line **216** to cause a video signal on the data line **217** to be charged and maintained in the pixel electrode **218**. To this end, the thin film transistor includes a gate electrode **221** connected to the gate line **216**, a source electrode **222** connected to the data line **217**, and a drain electrode **223** electrically connected to the pixel electrode **218**.

[0073] Further, the thin film transistor includes a plurality of insulation films **215a**, **215b**, and **215c** for insulation between these components and an active pattern **224** that forms a conductive channel between the source electrode **222** and the drain electrode **223** by a gate voltage supplied to the gate electrode **221**.

[0074] The active pattern **224** may be made of an amorphous silicon thin film, polycrystalline silicon thin film, or oxide semiconductor. For the active pattern **224** made of an amorphous silicon thin film, for example, the source/drain regions of the active pattern **224** are electrically connected to the source/drain electrodes via an ohmic-contact layer **225n** formed over the active pattern **224**.

[0075] According to the embodiment of the present invention, as the common electrodes **208**, pixel electrodes **218**, and data line **217** are bent to have the multi-domain structure allowing the liquid crystal molecules to be symmetrically driven, abnormal light caused by birefringence characteristics of liquid crystal can be canceled out to minimize a color shift phenomenon. Namely, the color shift phenomenon occurs according to a visual field for viewing liquid crystal molecules due to the birefringence characteristics of the liquid crystal molecules, and in particular, a yellow shift is observed in a short axis direction of the liquid crystal molecules, and a blue shift is observed in a longer axis direction

of the liquid crystal molecules. Thus, the birefringence value can be compensated by appropriately disposing the shorter and longer axis of the liquid crystal molecules to reduce or remove the color shift.

[0076] The array substrate **210** thus configured according to the embodiment of the present invention is characterized in that it has a COT structure in which the color filters **207** are formed over the thin film transistor.

[0077] The liquid crystal display device according to the embodiment of the present invention thus configured is characterized in that, instead of eliminating the existing black matrix, a light blocking pattern **228** made of an opaque conductive material is formed at the left and right boundaries of the pixel regions and a light blocking layer **227** made of color pigments is laminated at the upper and lower boundaries of the pixel regions.

[0078] The light blocking pattern **228** is formed over the data line **217** to cover the data line **217**, thereby preventing color interference between neighboring sub-pixels.

[0079] The light blocking pattern **228** may have a triple-layer structure consisting of upper and lower layers with low reflectance and low transmittance and an intermediate layer as an intermediate medium, like the common electrodes **208** and the pixel electrodes **218**, when internal electrodes, i.e., the common electrodes **208** and the pixel electrodes **218**, are formed on the array substrate **210**.

[0080] That is, the common electrodes **208** may have a triple-layer structure consisting of lower and upper common electrode layers **208a** and **208c** with low reflection and transmission characteristics and an intermediate common electrode layer **208b** which is light-transmissive. The light blocking pattern **228** may have a triple-layer structure consisting of lower and upper light blocking pattern layers **228a** and **228c** with low reflection and transmission characteristics and an intermediate light blocking pattern layer **228b** which is light-transmissive.

[0081] One end of the common electrodes **208** and one end of the light blocking pattern **228** formed over the data line **217** are connected to a common electrode line **208L**, which is in parallel with the gate line **216**, and the common electrodes **208** and the light blocking pattern **228** are electrically connected to a common line **208I**, which is in parallel with the gate line **216**, via a second contact hole **240b**.

[0082] The pixel electrodes **218** may be made of the same material on the same plane as the common electrodes **208**. That is, the pixel electrodes **218** may have a triple-layer structure consisting of lower and upper pixel electrode layers **218a** and **218c** with low reflection and transmission characteristics and an intermediate pixel electrode layer **218b** which is light-transmissive.

[0083] One end of the pixel electrodes **218** are connected to a pixel electrode line **218L**, which is in parallel with the gate line **216**, and the pixel electrode line **218L** is electrically connected to the drain electrode **223** of the thin film transistor exposed via a first contact hole **240a**.

[0084] A reference voltage for driving the liquid crystals, i.e., a common voltage, is supplied to the thus-configured common electrodes **208** via the common line **208I**. Accordingly, a horizontal electric field is formed between the pixel electrodes **218** supplied with a pixel voltage signal and the common electrodes **208** supplied with a common voltage. This horizontal electric field causes the liquid crystal molecules arranged in a horizontal direction between the array substrate **210** and the upper substrate **205** to rotate by dielec-

tric anisotropy. Light transmission through the pixel regions differs depending on the amount of rotation of the liquid crystal molecules, thereby displaying an image.

[0085] As described above, according to the embodiment of the present invention, the color filters **207** are formed on the same array substrate **210** as the thin film transistor so as to have a COT structure.

[0086] In an example, the color filters **207** include a red color filter **207R**, a green color filter **207G**, and a blue color filter **207B**, which are arranged in a repeating fashion along the length of the gate line **216**, but same color filters are repeated along the length of the data line **217**. The red color filter **207R**, green color filter **207G**, and blue color filter **207B** constitute a unit pixel, and the unit pixel displays an image having a predetermined color via colored light emitted through the red, green, and blue color filters.

[0087] FIG. 6 is a view illustrating a triple-layer structure of the light blocking pattern in the liquid crystal display device according to the embodiment of the present invention.

[0088] Referring to FIG. 6, the light blocking pattern **228** according to the embodiment of the present invention is characterized in that it has a triple-layer structure of upper and lower light blocking pattern layers **228c** and **228a** with low reflection and transmission characteristics and an intermediate light blocking pattern layer **228b** which is light-transmissive.

[0089] For example, the upper and lower light blocking pattern layers **228c** and **228a** may be made of an opaque conductive material such as ceramic, metal oxide, MoTi, or copper, and the intermediate light blocking pattern layer **228b** may be made of a transparent conductive material such as indium tin oxide (ITO) or indium zinc oxide (IZO).

[0090] By laminating the three layers of the light blocking pattern **228**, reflectance luminance can be improved by constructive and destructive interference of light using the reflection characteristics of the upper and lower layers and the transmission and refraction characteristics of the intermediate layer. For example, the reflectance of the entire light blocking pattern **228** is lowered using the reflection and transmission characteristics relative to the refractive index of ITO and the thickness of MoTi of the upper and lower layers. The path difference between light reflected by the upper light blocking pattern layer **228c** and light reflected by the lower light blocking pattern layer **228a** causes destructive interference.

[0091] The light blocking pattern **228** having the triple-layer structure can achieve black luminance since it has low reflection and transmission characteristics, as well as electric characteristics similar to those of conventional low-resistance electrodes. For example, it can be seen that the light blocking pattern **228** having the triple-layer structure consisting of MoTi/ITO/MoTi has a reflectance of about 13.43%, which is quite small compared to the conventional art (for example, about 61.0% for MoTi of 300 Å thickness).

[0092] The upper light blocking pattern layer **228c**, the intermediate light blocking pattern layer **228b**, and the lower light blocking pattern layer **228a** may have a thickness of 30 to 100 Å, 400 to 600 Å, and 100 to 300 Å, respectively.

[0093] For example, black luminance can be achieved by using the triple-layer structure of MoTi/ITO/MoTi, and although different according to other conditions, the best characteristics can be obtained when the upper MoTi layer has 30 Å thickness.

[0094] Moreover, the larger the thickness of the lower MoTi layer, the deeper the black luminance because of light cancellation at the upper and lower layers.

[0095] Hereinafter, a method of fabricating a liquid crystal display device will be described in detail with reference to the accompanying drawings.

[0096] FIGS. 7A to 7H are top plan views sequentially showing a fabrication process of the array substrate of FIG. 5 according to an embodiment of the present invention.

[0097] FIGS. 8A to 8H are cross-sectional views sequentially showing a fabrication process of the array substrate of FIG. 5 according to an embodiment of the present invention.

[0098] As shown in FIGS. 7A and 8A, a gate electrode **221**, a gate line **216**, and a common line **208/** are formed on an array substrate **210** made of a transparent insulation material such as glass.

[0099] The gate electrode **221**, the gate line **216**, and the common line **208/** are formed by depositing a first conductive film on the entire surface of the array substrate **210** and selectively patterning the first conductive film by a photolithography process.

[0100] The first conductive film may be made of a low-resistance, opaque conductive material such as aluminum Al, aluminum alloy, Al alloy, tungsten W, copper Cu, chromium Cr, molybdenum Mo such as MoTi. Moreover, the first conductive film may have a multilayer structure where two or more low-resistance materials are laminated.

[0101] While the common line **208/** is formed adjacent to the upper or lower side of the gate line **216**, the common line **208/** may be formed in a direction substantially parallel to the gate line **216**. However, the present invention is not limited to this.

[0102] Next, as shown in FIGS. 7B and 8B, a gate insulation film **215a**, an amorphous silicon thin film, and an n+ amorphous silicon thin film are formed on the entire surface of the array substrate **210** where the gate electrode **221**, the gate line **216**, and the common line **208/** are formed.

[0103] Afterwards, an active pattern **224** made of the amorphous silicon thin film is formed over the gate electrode **221** of the array substrate **210** by selectively removing the amorphous silicon thin film and the n+ amorphous silicon thin film by a photolithography process.

[0104] Hereupon, an n+ amorphous silicon thin film pattern **225**, which is made of the n+ amorphous silicon thin film and patterned in the same manner as the active pattern **224**, is formed over the active pattern **224**.

[0105] Next, as shown in FIGS. 7C and 8C, a second conductive film is formed on the entire surface of the array substrate **210** where the active pattern **224** and the n+ amorphous silicon thin film pattern **225** are formed.

[0106] The second conductive film may be made of a low-resistance, opaque conductive material such as aluminum Al, aluminum alloy, Al alloy, tungsten W, copper Cu, chromium Cr, molybdenum Mo such as MoTi, in order to form a source electrode, a drain electrode, and a data line. Moreover, the second conductive film may have a multilayer structure where two or more low-resistance materials are laminated.

[0107] Afterwards, a source electrode **222** and drain electrode **223** made of the second conductive film are formed over the active pattern **224** by selectively removing the n+ amorphous silicon thin film and the second conductive film by a photolithography process.

[0108] In addition, a data line 217 defining pixel regions, together with the gate line 216, is formed on the array substrate 210 by the photolithography process.

[0109] Hereupon, an ohmic-contact layer 225 n made of the n^+ amorphous silicon thin film is formed over the active pattern 224 to make an ohmic-contact between the source/drain regions of the active pattern 224 and the source/drain electrodes 222 and 223.

[0110] The data line 217, along with common electrodes and pixel electrodes to be formed later, may be bent to have a multi-domain structure allowing the liquid crystal molecules to be symmetrically driven.

[0111] While the embodiment of the present invention has been illustrated by taking an example where the active pattern 224, ohmic-contact layer 225 n , and data line, i.e., the source electrode 222, drain electrode 223, and data line 217, are individually formed by performing a masking process twice, the present invention is not limited to this example. The active pattern 224, ohmic-contact layer 225 n , and data line may be formed by performing a mask process only once using a half-tone mask or diffraction mask.

[0112] Next, as shown in FIGS. 7D to 7F and FIGS. 8D to 8F, an interlayer insulation film 215 b is formed on the entire surface of the array substrate 210.

[0113] The interlayer insulation film 215 b may be an inorganic insulation film such as a silicon nitride film SiN x or silicon oxide film SiO $_2$ or an organic insulation film such as photoacryl.

[0114] Afterwards, red, green, and blue color filters 207R, 207G, and 207B are formed within the pixel regions of the array substrate 210 where the interlayer insulation film 215 b is formed.

[0115] Hereupon, a light blocking layer 227 is formed in vertical black matrix regions through which the gate line 216 and the common line 208/ pass by mixing color pigments for the red, green, and blue color filters 207R, 207G, and 207B and laminating them.

[0116] Specifically, as shown in FIGS. 7D and 8D, a red color filter 207R is formed within a red sub-pixel by applying a red color pigment to the entire surface of the array substrate 210 where the interlayer insulation film 215 b is formed and then patterning it by a photolithography process. Hereupon, a red color layer 207 r made of the red color pigment may be formed in the vertical black matrix regions.

[0117] Next, as shown in FIG. 7E and FIG. 8E, a green color filter 207G is formed within a red sub-pixel by applying a green color pigment to the entire surface of the array substrate 210 where the red color filter 207R and the red color layer 207 r are formed and then patterning it by a photolithography process.

[0118] Next, as shown in FIG. 7F and FIG. 8F, a blue color filter 207B is formed within a blue sub-pixel by applying a blue color pigment to the entire surface of the array substrate 210 where the green color filter 207G is formed and then patterning it by a photolithography process. Hereupon, a blue color layer 207 b made of the blue color pigment may be formed in the vertical black matrix regions where the red color layer 207 r is formed. The red color layer 207 r and blue color layer 207 b laminated in the vertical black matrix regions constitute the light blocking layer 227.

[0119] Next, as shown in FIG. 7G and FIG. 8G, a passivation film 215 c is formed on the entire surface of the array substrate 210 where the color filters 207 are formed.

[0120] Afterwards, a first contact hole 240 a and a second contact hole 240 b that expose part of the drain electrode 223 and part of the common line 208/, respectively, by selective removing the gate insulation film 215 a , the interlayer insulation film 215 b , and the passivation film 215 c by a photolithography process. However, the present invention is not limited to this, and the first contact hole 240 a and the second contact hole 240 b may be formed after the above-mentioned interlayer insulation film 215 b is formed. In this case, the above-described red, green, and blue color filters 207R, 207G, and 207B are patterned in a way that exposes the first and second contact holes 240 a and 240 b .

[0121] Next, as shown in FIG. 7H and FIG. 8H, a third conductive film, a fourth conductive film, and a fifth conductive film are formed on the entire surface of the array substrate 210 where the passivation film 215 c is formed.

[0122] The fifth and third conductive films may be made of an opaque conductive material such as ceramic, metal oxide, MoTi, or copper to constitute common electrodes, pixel electrodes and upper and lower light blocking pattern layers, and the fourth conductive film may be made of a transparent conductive material such as ITO or IZO to constitute the common electrodes, the pixel electrodes, and an intermediate light blocking pattern layer.

[0123] The fifth conductive layer, fourth conductive layer, and third conductive layer may have a thickness of 30 to 100, 400 to 600 and 100 to 300 Å, respectively.

[0124] Afterwards, a plurality of common electrodes 208 and pixel electrodes 218 made up of the third, fourth, and fifth conductive films are formed within the pixel regions by selectively removing the third, fourth, and fifth conductive films by a photolithography process.

[0125] By selectively removing the third, fourth, and fifth conductive films by a photolithography process, a light blocking pattern 228 is formed at the left and right boundaries of the pixel regions, i.e., in horizontal black matrix regions, so as to cover the data line 217. That is, the light blocking pattern 228 may be formed in a way that opens as wide as possible within the vertical black matrix regions, in order to reduce internal reflection caused by the light blocking pattern 228.

[0126] Specifically, the common electrodes 208 may have a triple-layer structure consisting of lower and upper common electrode layers 208 a and 208 c with low reflection and transmission characteristics and an intermediate common electrode layer 208 b which is light-transmissive. The light blocking pattern 228 may have a triple-layer structure consisting of lower and upper light blocking pattern layers 228 a and 228 c with low reflection and transmission characteristics and an intermediate light blocking pattern layer 228 b which is light-transmissive.

[0127] One end of the common electrodes 208 and one end of the light blocking pattern 228 formed over the data line 217 are connected to a common electrode line 208L, which is in parallel with the gate line 216, and the common electrodes 208 and the light blocking pattern 228 are electrically connected to a common line 208L, which is parallel with the gate line 216, via the second contact hole 240 b .

[0128] The pixel electrodes 218 may be made of the same material on the same plane as the common electrodes 208. That is, the pixel electrodes 218 may have a triple-layer structure consisting of lower and upper pixel electrode layers 218 a and 218 c with low reflection and transmission characteristics and an intermediate pixel electrode layer 218 b which is light-transmissive.

[0129] One end of the pixel electrodes **218** are connected to a pixel electrode line **218L**, which is in parallel with the gate line **216**, and the pixel electrode line **218L** is electrically connected to the drain electrode **223** of the thin film transistor exposed via a first contact hole **240a**.

[0130] The common electrodes **208**, the pixel electrodes **218**, and the light blocking pattern **228** may have a bent structure like the data line **217** as described above.

[0131] Afterwards, the array substrate **210** thus configured is attached to the upper substrate facing it by a sealant formed on the outer edge of an image display area, with a predetermined cell gap maintained between them by a column spacer.

[0132] The thus-configured liquid crystal display device according to the embodiment of the present invention is applicable to an image panel of a polarized glasses-type stereoscopic image display device. In this case, the light blocking layer can solve the vertical viewing angle problem of the polarized glasses-type stereoscopic image display device as it constitutes black stripes.

[0133] FIG. 9 is a view illustrating the structure of a stereoscopic image display device using the liquid crystal display device of the present invention as an image panel.

[0134] First of all, a 3D display can be simply defined as “a total system for artificially reproducing a 3D image.”

[0135] This system includes a software technique for displaying an image in 3D and a hardware technique for actually rendering content created by this software technique into 3D. The reason why the software technique is included is because 3D display hardware requires content created in a different software approach for a different stereoscopic display method.

[0136] A virtual 3D display is a total system that gives a literally virtual 3D effect on planar display hardware using binocular disparity, one of the factors giving a 3D effect, which results from the eyes' horizontal separation by about 65 mm. In other words, our eyes have slightly different views of the same object (more precisely, the left and right eyes see slightly different spatial information) due to binocular disparity, and the brain accurately combines these two views coming from the retinæ to give us a 3D view. Using binocular display image, the virtual 3D display is designed to create a virtual 3D effect by presenting two left and right images on a 2D display device and providing them to the left and right eyes.

[0137] In order for the virtual 3D display device to display images from two channels on a single screen, the images are output from the channels one by one in an alternating manner in a horizontal or vertical direction on a single screen. Once the two images from the two channels are output from a single display device, a right image is input to the right eye and a left image is input to the left eye in case of an auto-stereoscopic method due to a hardware structure. In case of a stereoscopic method using glasses, a right image is blocked so as not to be viewed by the left eye, and a left image is blocked so as not to be viewed by the right eye, by using special glasses.

[0138] Methods for displaying stereoscopic images are categorized largely into glasses-type methods and non-glasses type methods.

[0139] The glasses-type methods include an anaglyph method using red and cyan glasses for the left and right eyes, respectively, a polarized glasses method using polarized glasses with different directions of polarization for the left eye and the right eye, and a liquid crystal shutter method that periodically repeats a time-divided image and uses liquid

crystal (LC) shutter glasses synchronized with the period of the time-divided image. Among these methods, the polarized glasses method has the advantage of easily rendering two 2D images into 3D images.

[0140] Referring to FIG. 9, the polarized glasses method is a method for spatially separating right and left images from each other by arranging a patterned retarder **300** on the front surface of an image panel **200**, using a polarization phenomenon.

[0141] The patterned retarder **300** of the polarized glasses-type stereoscopic image display device indicates a film where predetermined patterns are formed at corresponding positions so that right and left images are polarized perpendicular to one other.

[0142] For instance, the patterned retarder **300** is provided with a glass substrate. Although not shown, an alignment layer and a bi-refractive layer are formed on the glass substrate. The alignment layer and the bi-refractive layer are provided with regular patterns of a first region **300a**, and regular patterns of a second region **300b**. The first region **300a** and the second region **300b** are formed of strips alternating with each other to correspond to image lines of the image panel **200**. The first and second regions **300a** and **300b** have the same alignment direction. The first region **300a** and the second region **300b** may also have different alignment directions, e.g., about 45° and 135°.

[0143] The image panel **200** may be configured as one of a Liquid Crystal Display (LCD) device, a Field Emission Display (FED) device, a Plasma Display Panel (PDP) and an Electroluminescent Display (EL) device. If the image panel **200** is configured as an LCD device, an upper polarizing plate **311** having a light absorption axis in a horizontal direction is disposed between the image panel **200** and the patterned retarder **300**. Although not shown, a backlight unit is disposed below the image panel **200**, and a lower polarizing plate is disposed between the image panel **200** and the backlight unit.

[0144] The upper polarizing plate **311** is an analyzer attached onto the upper glass substrate of the image panel **200**, which passes therethrough only specific linearly-polarized light, among light incident after passing through an LC layer of the image panel **200**.

[0145] A widely-used 3D display method is a method for displaying right and left images on odd and even lines, or on even and odd lines, respectively. That is, as shown, ‘L’ images are disposed in odd lines and ‘R’ images are disposed in even lines in a vertical direction. Once the ‘L’ and ‘R’ images are displayed on the image panel **200**, the viewer can appreciate 3D images by separately viewing the ‘L’ and ‘R’ images using stereoscopic glasses **400**.

[0146] As aforementioned, the patterned retarder **300** is provided with regular patterns of a first region **300a** and regular patterns of a second region **300b**, the regular patterns arranged on odd and even lines in an alternating manner. For instance, the regular patterns of the first region **300a** and the regular patterns of the second region **300b** may be arranged on odd and even lines so as to form +45° and -45° with an absorption axis of the upper polarizing plate **311**, respectively. The regular patterns of the first region **300a** and the regular patterns of the second region **300b** implement phase retardation of light by $\lambda/4$ using a bi-refractive medium. A light axis of the regular patterns of the first region **300a** is orthogonal to a light axis of the regular patterns of the second region **300b**. Therefore, the regular patterns of the first region **300a** are arranged to face lines where the ‘L’ images of the

image panel **200** are displayed, and are configured to convert light of the 'L' images to first polarized light (circularly or linearly polarized light). And, the regular patterns of the second region **300b** are arranged to face lines where the 'R' images of the image panel **200** are displayed, and are configured to convert light of the 'R' images to second polarized light (circularly or linearly polarized light). For instance, the regular patterns of the first region **300a** may be implemented as a polarizing filter for passing left-handed circular polarization therethrough, and the regular patterns of the second region **300b** may be implemented as a polarizing filter for passing right-handed circular polarization therethrough.

[0147] A polarizing film for passing therethrough only a first polarizing component is attached to a left-eye lens of the stereoscopic glasses **400**, and a polarizing film for passing therethrough only a second polarizing component is attached to a right-eye lens of the stereoscopic glasses **400**. Therefore, a viewer wearing the stereoscopic glasses **400** can appreciate images as 3D images by viewing the 'L' images with the left eye, and by viewing the 'R' images with the right eye.

[0148] In the present invention, the polarized glasses method is implemented as a circularly polarizing method. However, the present invention is not limited to this. That is, the polarized glasses method may be also implemented as a linearly polarizing method.

[0149] In the polarized glasses-type stereoscopic image display device thus configured, predetermined black stripes BS are formed at the upper and lower boundaries of pixels P. For example, a light blocking layer formed on the lower glass substrate of the image panel **200** may be used as the black stripes BS.

[0150] In the 3D display method for displaying right and left images on odd and even lines, or on even and odd lines, respectively, 'L' and 'R' images vertically adjacent to each other are separated from each other by the black stripes BS made up of the light blocking layer, so that the 'L' images are input to the left eye and the 'R' images are input to the right eye.

[0151] While the embodiment of the present invention has been described taking as an example an amorphous silicon thin film transistor using an amorphous silicon thin film as an active pattern, the present invention is not limited to this example and can be applied to a polycrystalline silicon thin film transistor using a polycrystalline silicon thin film or an oxide thin film transistor using oxide semiconductor.

[0152] Furthermore, the present invention may be applicable to other display devices fabricated using a thin film transistor, for example, an organic electroluminescent display device with an organic light emitting diode OLED connected to a driving transistor.

[0153] It will be apparent to those skilled in the art that various modifications and variations can be made in the present invention without departing from the spirit or scope of the invention. Thus, it is intended that the present invention cover the modifications and variations of this invention provided they come within the scope of the appended claims and their equivalents.

What is claimed is:

1. A method of fabricating a liquid crystal display device, the method comprising the steps of:

forming a gate line and a data line that cross each other on a first substrate to define red, green, and blue pixel regions;

forming a thin film transistor at the crossing of the gate line and the data line;

forming red, green, and blue color filters within the red, green, and blue pixel regions of the first substrate;

forming a light blocking layer at upper and lower boundaries of the pixel regions by laminating color pigments for the red, green, and blue color filters;

forming a plurality of common electrodes and pixel electrodes within the pixel regions of the first substrate where the red, green, and blue color filters and the light blocking layer are formed;

forming a light blocking pattern at left and right boundaries of the pixel regions over the data line; and

attaching the first substrate and a second substrate together, wherein the common electrodes, the pixel electrodes, and the light blocking pattern have a triple-layer structure consisting of lower and upper layers with low reflection and transmission characteristics; and an intermediate layer that is light-transmissive.

2. The method of claim 1, further comprising of forming a common line parallel to the gate line, wherein the common line is adjacent an upper or lower side of the gate line.

3. The method of claim 2, wherein one end of the common electrodes and one end of the light blocking pattern are connected to a common electrode line, which is parallel with the gate line, and wherein the common electrode line is electrically connected to the underlying common line.

4. The method of claim 1, wherein one end of the pixel electrodes is connected to a pixel electrode line, which is in parallel with the gate line, and wherein the pixel electrode line is electrically connected to the drain electrode of the thin film transistor.

5. The method of claim 1, wherein the upper and lower layers of the common electrodes, pixel electrodes, and light blocking pattern are made of an opaque conductive material.

6. The method of claim 5, wherein the opaque conductive material is ceramic, metal oxide, MoTi, or copper.

7. The method of claim 1, wherein the intermediate layers of the common electrodes, pixel electrodes, and light blocking pattern are made of a transparent conductive material.

8. The method of claim 7, wherein the transparent conductive material is indium tin oxide (ITO) or indium zinc oxide (IZO).

9. The method of claim 1, wherein the upper layers, intermediate layers, and lower layers of the common electrodes, pixel electrodes, and light blocking pattern have a thickness of 30 to 100 Å, 400 to 600 Å, and 100 to 300 Å, respectively.

10. The method of claim 1, wherein the light blocking layer has a lamination structure of red and blue color layers made of color pigments for the red and blue color filters.

11. A liquid crystal display device comprising:

a gate line and a data line formed on a first substrate and crossing each other to define red, green, and blue pixel regions;

a thin film transistor formed at the crossing of the gate line and the data line;

red, green, and blue color filters formed within the red, green, and blue pixel regions of the first substrate where the thin film transistor is formed;

a light blocking layer formed at upper and lower boundaries of the pixel regions by laminating color pigments for the red, green, and blue color filters;

a plurality of common electrodes and pixel electrodes formed within the pixel regions of the first substrate where the red, green, and blue color filters and the light blocking layer are formed;

a light blocking pattern formed at left and right boundaries of the pixel regions over the data line; and

a second substrate attached to the first substrate and facing each other,

wherein the common electrodes, the pixel electrodes, and the light blocking pattern have a triple-layer structure consisting of lower and upper layers with low reflection and transmission characteristics, and an intermediate layer which is light-transmissive.

12. The liquid crystal display device of claim **11**, further comprising a common line formed in parallel with the gate line, wherein the common line is adjacent to an upper or lower side of the gate line.

13. The liquid crystal display device of claim **12**, wherein one end of the common electrodes and one end of the light blocking pattern are connected to a common electrode line, which is in parallel with the gate line, and wherein the common electrode line is electrically connected to the underlying common line.

14. The liquid crystal display device of claim **11**, wherein one end of the pixel electrodes is connected to a pixel electrode line, which is in parallel with the gate line, and wherein the pixel electrode line is electrically connected to the drain electrode of the thin film transistor.

15. The liquid crystal display device of claim **11**, wherein the upper and lower layers of the common electrodes, pixel electrodes, and light blocking pattern are made of an opaque conductive material.

16. The liquid crystal display device of claim **15**, wherein the opaque conductive material is ceramic, metal oxide, MoTi, or copper.

17. The liquid crystal display device of claim **11**, wherein the intermediate layer of the common electrodes, pixel electrodes, and light blocking pattern is made of a transparent conductive material.

18. The liquid crystal display device of claim **17**, wherein the transparent conductive material is indium tin oxide (ITO) or indium zinc oxide (IZO).

19. The liquid crystal display device of claim **11**, wherein the light blocking layer has a lamination structure of red and blue color layers made of color pigments for the red and blue color filters.

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专利名称(译)	液晶显示装置及其制造方法		
公开(公告)号	US20150138480A1	公开(公告)日	2015-05-21
申请号	US14/547212	申请日	2014-11-19
[标]申请(专利权)人(译)	乐金显示有限公司		
申请(专利权)人(译)	LG DISPLAY CO. , LTD.		
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发明人	YI, HYOJONG CHOI, DONGLN		
IPC分类号	G02F1/1335 H01L27/12 G02F1/1362		
CPC分类号	G02F1/133514 G02F1/136286 G02F1/136209 G02F2001/136222 H01L27/124 H01L27/1259 G02F1/133516 G02F2001/134318 G02F1/133502 G02F1/134363 G02F1/13439 G02F1/133512		
优先权	1020130141701 2013-11-20 KR		
其他公开文献	US9268168		
外部链接	Espacenet USPTO		

摘要(译)

提供一种具有用于高图像质量的TFT (COT) 结构的滤色器，高性能显示器及其制造方法的液晶显示装置，以通过层叠彩色颜料来减小像素部分和外部部分之间的亮度差异。黑矩阵区域，形成用作黑矩阵的光阻挡图案，并且将光阻挡图案配置为具有三层以实现黑色亮度。

